AFRL-SN-WP-TP-2004-101

MODELING AND CHARACTERIZATION OF DIELECTRIC-CHARGING EFFECTS IN RF MEMS CAPACITIVE SWITCHES

Xiaobin Yuan, James C.M. Hwang, David Forehand, and Charles L. Goldsmith

December 2004

STINFO FINAL REPORT

SENSORS DIRECTORATE
AIR FORCE RESEARCH LABORATORY
AIR FORCE MATERIEL COMMAND
WRIGHT-PATTERSON AIR FORCE BASE, OH 45433-7320

NOTICE

Using government drawings, specifications, or other data included in this document for any purpose other than government procurement does not in any way obligate the U.S. Government. The fact that the government formulated or supplied the drawings, specifications, or other data does not license the holder or any other person or corporation; or convey and rights or permission to manufacture, use, or sell any patented invention that may relate to them.

This report has been reviewed by the Air Force Research Laboratory Wright Site Office of Public Affairs (AFRL/WS/PA) and is releasable to the National Technical Information Service (NTIS). At NTIS, it will be available to the general public, including foreign nationals.

This technical report has been reviewed and is approved for publication.

_____//s//_____   _____//s//_____
JOHN L. EBEL   KENICHI NAKANO, Chief
Electron Devices Branch   Electron Devices Branch
Aerospace Components Division   Aerospace Components Division

_____//s//_____
ROBERT T. KEMERLEY, Chief
Aerospace Components Division
Sensors Directorate

Copies of this report should not be returned unless return is required by security considerations, contractual obligations, or notice on a specific document.

REPORT DOCUMENTATION PAGE

1. REPORT DATE *(DD-MM-YY)*	2. REPORT TYPE	3. DATES COVERED *(From - To)*
December 2004	Conference paper preprint	

4. TITLE AND SUBTITLE
MODELING AND CHARACTERIZATION OF DIELECTRIC-CHARGING EFFECTS IN RF MEMS CAPACITIVE SWITCHES

5a. CONTRACT NUMBER
F33615-03-C-7003

5b. GRANT NUMBER

5c. PROGRAM ELEMENT NUMBER
69199F

6. AUTHOR(S)
Xiaobin Yuan and James C.M. Hwang (Lehigh University)
David Forehand
Charles L. Goldsmith (MEMtronics Corp.)

5d. PROJECT NUMBER
ARPS

5e. TASK NUMBER
ND

5f. WORK UNIT NUMBER
AN

7. PERFORMING ORGANIZATION NAME(S) AND ADDRESS(ES)

MEMtronics Corp.
Plano, TX 75075

Lehigh University
Bethlehem, PA 18015

8. PERFORMING ORGANIZATION REPORT NUMBER

9. SPONSORING/MONITORING AGENCY NAME(S) AND ADDRESS(ES)

Sensors Directorate
Air Force Research Laboratory
Air Force Materiel Command
Wright-Patterson AFB, OH 45433-7334

10. SPONSORING/MONITORING AGENCY ACRONYM(S)
AFRL/SNDD

11. SPONSORING/MONITORING AGENCY REPORT NUMBER(S)
AFRL-SN-WP-TP-2004-101

12. DISTRIBUTION/AVAILABILITY STATEMENT
Approved for public release; distribution is unlimited.

13. SUPPLEMENTARY NOTES
Paper contains color. To be presented at the 2005 IEEE International Microwave Symposium, Long Beach, CA, June 11-17, 2005. This work, resulting partially from Department of Defense Air Force contract number F33615-03-C-7003, has been submitted for publication in the Proceedings of the 2005 IEEE International Microwave Symposium. If published, IEEE may assert copyright. If so, the United States has for itself and others acting on its behalf an unlimited, paid-up, nonexclusive, irrevocable worldwide license. Any other form of use is subject to copyright restrictions.

14. ABSTRACT
For the first time, charging and discharging of traps in the dielectric of state-of-the art RF MEMS capacitive switches were characterized in detail. Densities and time constants of different trap species were extracted under different control voltages. It was found that, while charging and discharging time constants are relatively independent of control voltage, steady-state charge densities increase exponentially with control voltage. A simple charge model was constructed to predict the amount of charge injected into the dielectric and the corresponding shift in actuation voltage. Good agreement was obtained between the model prediction and experimental data.

15. SUBJECT TERMS
Microelectromechanical Systems (MEMS), Radio Frequency (RF), Microwave Devices

16. SECURITY CLASSIFICATION OF:			17. LIMITATION OF ABSTRACT:	18. NUMBER OF PAGES	19a. NAME OF RESPONSIBLE PERSON (Monitor)
a. REPORT Unclassified	**b. ABSTRACT** Unclassified	**c. THIS PAGE** Unclassified	SAR	10	John L. Ebel

19a. NAME OF RESPONSIBLE PERSON (Monitor)
John L. Ebel
19b. TELEPHONE NUMBER *(Include Area Code)*
(937) 255-1874, ext. 3462

Modeling and Characterization of Dielectric-Charging Effects in RF MEMS Capacitive Switches

Xiaobin Yuan, *Student Member, IEEE,* James C. M. Hwang, *Fellow, IEEE,* David Forehand, *Member, IEEE,* and Charles L. Goldsmith, *Senior Member, IEEE*

Abstract — For the first time, charging and discharging of traps in the dielectric of state-of-the-art RF MEMS capacitive switches were characterized in detail. Densities and time constants of different trap species were extracted under different control voltages. It was found that, while charging and discharging time constants are relatively independent of control voltage, steady-state charge densities increase exponentially with control voltage. A simple charge model was constructed to predict the amount of charge injected into the dielectric and the corresponding shift in actuation voltage. Good agreement was obtained between the model prediction and experimental data.

Index Terms — RF, MEMS, switch, dielectric, charging, trap.

I. INTRODUCTION

The commercialization of RF MEMS devices is hindered by a number of factors such as reliability and packaging. In particular, the lifetime of electrostatically actuated RF MEMS capacitive switches can be affected by dielectric-charging effects [1]. The dielectric is typically low-temperature deposited silicon dioxide or nitride with a high density ($10^{18}/cm^3$) of traps associated with silicon dangling bonds. During switch operation, the electric field across the dielectric can be as high as 10^6 V/cm causing electrons or holes to be injected into the switch dielectric and become trapped. With repeated operation, charge gradually builds up in the dielectric resulting in actuation-voltage shift and/or stiction [2].

Although a general charge model exists in the literature [3], there has been no effort to accurately model the charging state of the dielectric and its impact on actuation voltage. Using a special test structure and setup, we directly characterized charging and discharging currents in state-of-the-art RF MEMS
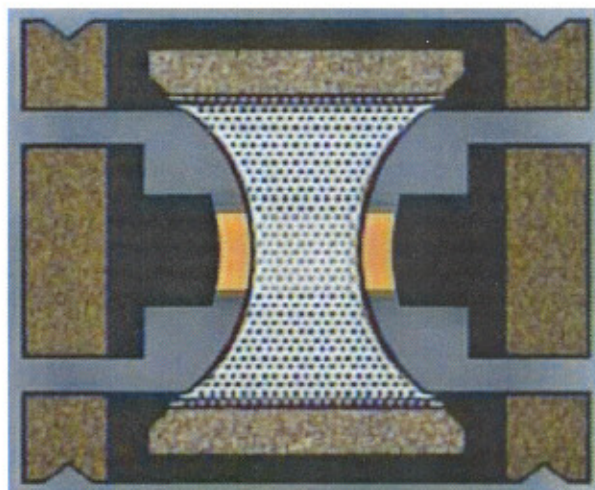
Fig. 1. Top view of a state-of-the-art RF MEMS capacitive switch.

capacitive switches and constructed a simple charge model to predict their effects on the operation of the switches under different control voltages. The model was found to be in good agreement with measured actuation-voltage shift.

II. EXPERIMENTAL

Fig. 1 illustrates a state-of-the-art metal-dielectric-metal RF MEMS capacitive switch fabricated on a glass substrate. The dielectric is sputtered silicon dioxide with a thickness of 0.25 µm and a dielectric constant of 4.0. The top electrode is a 0.3-µm-thick flexible aluminum membrane that is grounded. The bottom chromium/gold electrode serves as the center conductor of a 50 Ω coplanar waveguide for the RF signal. Without any electrostatic force, the membrane is normally suspended in air 2.5 µm above the dielectric. Control voltage in the range of 25-35 V is applied to the bottom electrode, which brings the membrane in contact with the dielectric thus forming a 120 µm x 80 µm capacitor. The switch has low insertion loss (0.06 dB) and reasonable isolation (15 dB) at 35 GHz. The switching time is less than 10 µs. Details of the design, fabrication and performance of the switches will be reported elsewhere.
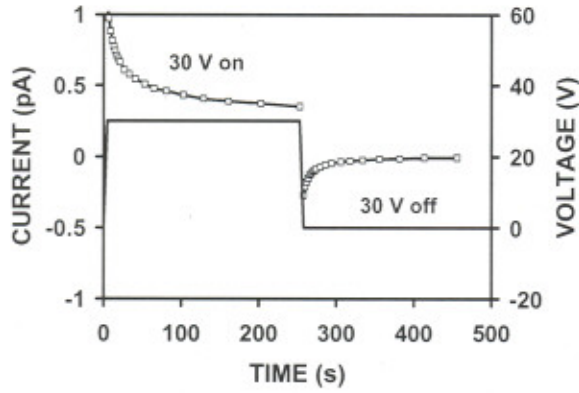
Fig. 2. Measured charging current under 30 V and discharging current after removal of the voltage on an MIM test structure. Solid line is the control voltage waveform.

In order to quantitatively characterize the trap states of the dielectric, charging and discharging current transients [4] were measured on switches whose membrane was intentionally fabricated in a permanently down position (without the sacrificial release layer) thus resembling a metal-insulator-metal capacitor. A precision semiconductor parameter analyzer was used to force a voltage pulse onto the switch while sensing the current transient. Using a well-guarded probe station and probes suppressed the capacitive and leakage currents in the measurement path, extending the transient current measurement range below pA level.

As shown in Fig. 2, when a voltage pulse is applied to a permanently down switch, the total current includes displacement current, trap charging current and steady-state leakage current. After this voltage is removed, charges accumulated on the electrodes and the dielectric begin to discharge. Since the time constant for the displacement current is of the order of milliseconds, the current transients shown in Fig. 2 comprise mainly trap charging and discharging currents. In this case, trap density, charging and discharging time constants can be extracted for different trap species.
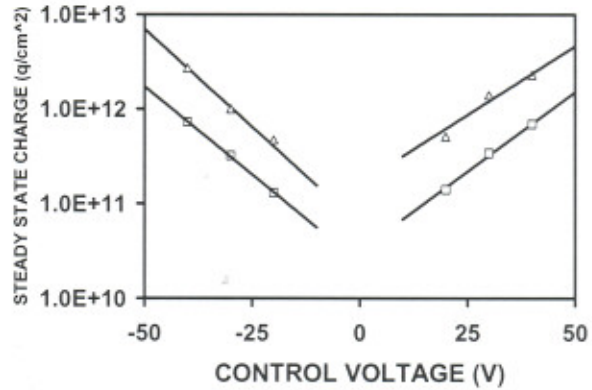
III. MEASUREMENT RESULTS AND MODEL EXTRACTION

The amount of charge trapped in the dielectric can be modeled as

$$Q = \sum_{J} Q^J [1 - \exp(-t_{ON}/\tau_C^J)]\exp(-t_{OFF}/\tau_D^J) \quad (1)$$

where Q^J is the steady-state charge density of the Jth species of trap, τ_C and τ_D are the charging and discharging time constants, t_{ON} and t_{OFF} are the on and off times of the switch corresponding to the charging and discharging times.
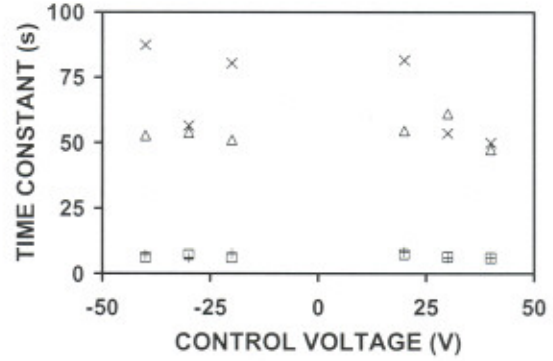

(a)

(b)

Fig. 3. (a) Trap 1 (□) charging and (+) discharging and trap 2 (Δ) charging and (x) discharging time constants and (b) (symbols) extracted and (lines) fitted steady-state charge density for (□) trap 1 and (Δ) trap 2 under -40, -30, -20, 20, 30 and 40 V.

Switch lifetime has exhibited an exponential dependence on the control voltage [1], implying that either the charge density or the time constant is strongly dependent on voltage. To investigate the voltage dependence of the model parameters, charging and discharging currents were measured on permanently down switches under control voltages both above and below the actuation voltage of normal switches. Then the model parameters (Q^J, τ_C and τ_D) were extracted for each control voltage by fitting the current transients with exponential functions. Two exponential functions, representing two trap species, were found to give good fit.

As shown in Fig. 3(a), the extracted charging and discharging time constants for both positive and negative control voltages exhibit no strong voltage dependence. Hence τ_C and τ_D were taken as the average of the time constants extracted under different voltages. By contrast, the steady-state charge density is found to vary exponentially with the control voltage, as illustrated in Fig. 3(b). The voltage dependence of the steady-state

2
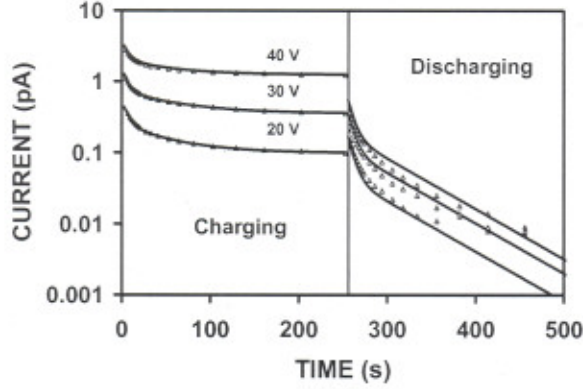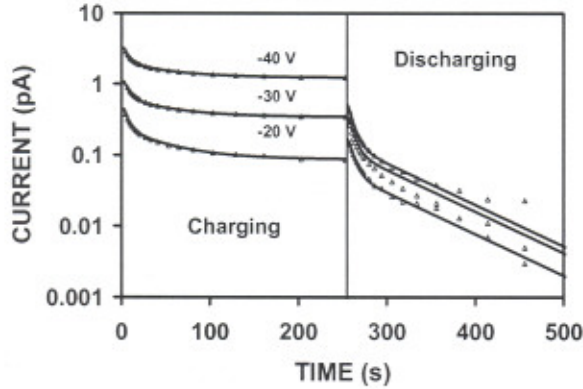
Fig. 4. (a) Absolute values of (symbols) measured and (lines) calculated charging and discharging current transients under 20, 30 and 40 V bottom up. (b) Absolute values of (symbols) measured and (lines) calculated charging and discharging current transients under −20, −30 and −40 V bottom up.

TABLE I
EXTRACTED MODEL PARAMETERS

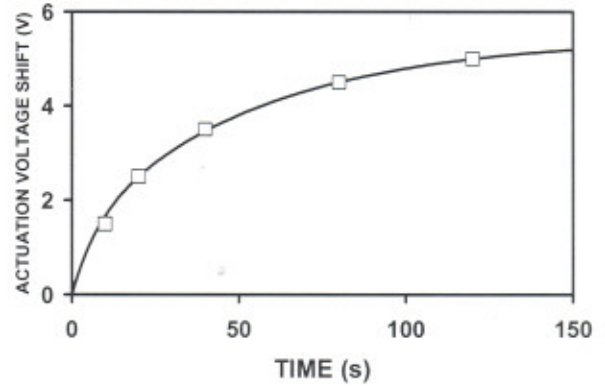|	τ_C (s)	τ_D (s)	Q_0 (cm^{-2})	V_0 (V)
POSITIVE BIAS				
J	τ_C (s)	τ_D (s)	Q_0 (cm^{-2})	V_0 (V)
1	6.6	6.8	3.1×10^{10}	12.9
2	54.3	61.6	1.6×10^{11}	14.9
NEGATIVE BIAS				
J	τ_C (s)	τ_D (s)	Q_0 (cm^{-2})	V_0 (V)
1	6.5	7.0	2.4×10^{10}	11.7
2	52.5	74.7	6.0×10^{10}	10.5

Fig. 5. (□) Measured and (—) modeled actuation-voltage shift after 10, 20, 40, 80 and 120 s of -30 V stress on the switch. The charge sheet is assumed to be 90 nm away from the bottom switch electrode.

charge density for the *Jth* trap is modeled as

$$Q^J = Q_0^J \exp(V / V_0^J) \qquad (2)$$

where V is the control voltage while Q_0 and V_0 are fitting parameters.

Using the above described approach, two sets of model parameters were extracted for positive and negative voltages as listed in Table I. The measured and calculated transient charging and discharging currents under different control voltages are plotted in Fig. 4 showing good agreement between experimental data and theoretical calculation.

IV. MODEL VERIFICATION

The dielectric charging effect on state-of-the-art RF MEMS capacitive switches (shown in Fig. 1 and fabricated on the same wafer as the permanently down switches) was measured by applying a stress voltage on the bottom electrode of the switch for different time periods while measuring the corresponding actuation voltage. The stress voltage used in the experiment is −30 V, which is sufficient to actuate the switch. After 120 s of stress, the actuation voltage was shifted by 5 V in the positive direction indicating injection of negative charges from the bottom electrode into the dielectric.

The actuation-voltage shift due to dielectric charging can be expressed as

$$\Delta V = qhQ / \varepsilon_0 \varepsilon_r \qquad (3)$$

where q is the electron charge, h is the distance between the bottom electrode and the trapped charge sheet, ε_0 is the permittivity of free space, and ε_r is relative dielectric constant of the switch dielectric insulator.

The injected charge density Q for certain stress period is predicted by the charge model (1) with h optimized to give the best fit between model prediction and experimental data. Fig. 5 shows the measured and modeled actuation-voltage shifts after different stress periods. Good agreement was obtained for all stresses by

using $h = 90$ nm, which is about one third of the dielectric thickness.

V. DISCUSSION

Although the present model assumes that the injected charge is an equivalent sheet of charge 90 nm above the bottom electrode, the actual bottom-injected electrons most likely are distributed across the thickness of the dielectric. Since their collective effect on the actuation voltage can be approximated by a sheet charge, it greatly simplifies the model making it possible to predict the dielectric-charging effect under complicated control-voltage waveforms. In addition, tunneling and trap-to-trap hopping were not taken into account in the present simple model so that (1) is only based on the first-order carrier capture and emission dynamics. Therefore, the extracted charging and discharging time constants should not be construed as exact capture and emission times, respectively.

The current transients measured on the permanently down switches were used to predict the dielectric-charging effect in functioning switches. Although charge injection from the bottom electrode is expected to be similar in both cases, charge injection from the top electrode can be rather different due to non-ideal contact between the top electrode and the dielectric in actual switches. For the present devices, the dielectric-charging effect is dominated by charge injection from the bottom so that any difference in charge injection from the top can be ignored. This may not be the case in other types of switches for which charge injection from the top is not negligible.

VI. CONCLUSION

Charging and discharging currents of traps in permanently down RF MEMS capacitive switches were measured. Based on the measured data, a simple charge model was extracted. The steady-state charge density was found to have an exponential dependence on the control voltage while the charging and discharging time constants were relatively independent of voltage. The extracted charge model was capable of accurately predicting charge-induced actuation-voltage shift in state-of-the-art MEMS capacitive switches.

REFERENCES

[1] C. Goldsmith, J. Ehmke, A. Malczewski, B. Pillans, S. Eshelman, Z. Yao, J. Brank, and M. Eberly, "Lifetime characterization of capacitive RF MEMS switches," in *IEEE MTT-S Dig.*, 2001, pp. 227-230.

[2] X. Yuan, S. V. Cherepko, J. C. M. Hwang, C. L. Goldsmith, C. Nordquist and C. Dyck, "Initial observation and analysis of dielectric-charging effects on RF MEMS capacitive switches," in *IEEE MTT-S Dig.*, 2004, pp. 1943-1946.

[3] W Merlijn van Spengen, Robert Puers, Robert Mertens and Ingrid De Wolf, "A comprehensive model to predict the charging and reliability of capacitive RF MEMS switches," *J. Micromechanics Microengineering*, vol. 14, pp. 514-521, Jan. 2004.

[4] H. Matsuura, M. Yoshimoto and H. Matsunami, "Discharging current transient spectroscopy for evaluating traps in insulators," *Japanese J. Appl. Phys.*, vol. 34, pp. L185-L187, Feb. 1995.